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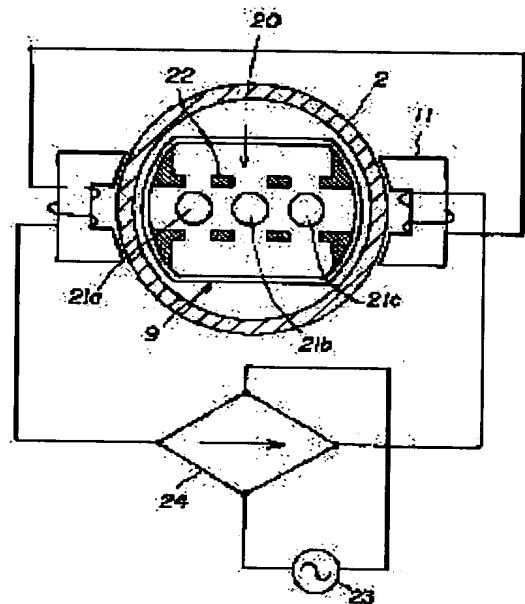
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## (54) DEFLECTED ABERRATION CORRECTION METHOD AND CATHODE-RAY TUBE

## (57)Abstract:

PROBLEM TO BE SOLVED: To provide a deflected aberration correction method for a cathode-ray tube, capable of correcting a deflected aberration in such a state as synchronized with deflection.

SOLUTION: Regarding a deflected aberration correction method for a cathode-ray tube equipped at least with a panel part having a phosphor screen formed thereon, a neck part housing an electron gun made of a plurality of electrodes, and a deflecting device mounted on a funnel part for jointing the panel part and the neck part to each other, a part of the electrodes forming the electron gun 9 housed in the neck part 2 is fitted with magnetic pieces 22 and a magnetic field generation device 11 is mounted on the outer wall of the neck part. Furthermore, magnetic field synchronized with deflected magnetic field formed through the deflecting device is generated with the magnetic field generation device 11 for the excitation of the magnetic pieces 22. The deflected aberration of an electron beam is thereby corrected.



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